In the claims:

Please substitute the following full listing of claims for the claims as originally filed or most recently amended.

1. (Currently amended) A lithography system, comprising:

a reticle chamber containing a reticle stage component extending between portions of an optics system,

said reticle chamber having a reticle chamber opening that provides direct access to ~~a~~ said reticle stage within ~~the~~ said reticle chamber so that ~~the~~ said reticle stage can be accessed or removed through ~~the~~ said reticle chamber opening and from between said portions of said optics system without disassembly of components of said optics system.

Claim 2 has been cancelled.

3. (Currently amended) The lithography system of claim 1, wherein ~~the~~ said reticle stage component includes a reticle stage and a reticle table, wherein said reticle stage component is removable from ~~the~~ said reticle chamber in a first direction which is in a plane substantially horizontal to ~~a~~ said reticle table mounted to ~~the~~ said reticle stage.

4. (Currently amended) The lithography system of claim ~~1~~ 21, wherein ~~a~~ said reticle chamber maintenance panel is pivotably mounted to ~~the~~ said reticle chamber.

5. (Currently amended) The lithography system of claim 1, wherein ~~the~~ said reticle chamber opening is at an angle substantially equal to or between 0° and 45° with relation to ~~the~~ said reticle chamber.

6. (Currently amended) The lithography system of claim 1, wherein ~~the~~ said reticle chamber opening is at an angle at or greater than 45° with relation to ~~the~~ said reticle chamber.

7. (Currently amended) The lithography system of claim 1, ~~further comprising~~ wherein said optics system comprises:

a projection optic system; and

an illuminator optic system; ~~and~~

wherein said ~~a~~ reticle table mounted to ~~the~~ said reticle stage ~~and~~ is positionable between ~~the~~ said projection optic system and ~~the~~ said illuminator optic system.

8. (Currently amended) The lithography system of claim ~~1~~ 7, wherein ~~a~~ said reticle table and ~~the~~ said reticle stage are removable through ~~the~~ said reticle chamber opening in a plane which is substantially perpendicular to a source illuminating from ~~the~~ said illuminator optic system.

9. (Currently amended) The lithography system of claim ~~1~~ 7, further comprising a body structure which is mounted to a lower portion of the reticle chamber, ~~a~~ said projection optic system and ~~an~~ said illuminator optic system being mounted to ~~the~~ said body structure.

10. (Currently amended) The lithography system of claim ~~1~~ 21, wherein ~~the~~ said reticle chamber maintenance panel is semi-cylindrically shaped.

Claim 11 has been cancelled.

12. (Currently amended) The lithography system of claim 1, wherein ~~the~~ said reticle chamber opening provides access to substantially a center of gravity of

~~the~~ said reticle stage.

13. (Currently amended) A lithography system, comprising:

a reticle chamber having a reticle chamber angled opening,

a reticle chamber maintenance panel which is removably mounted to the reticle chamber over ~~the~~ said reticle chamber angled opening;

an optical system for illuminating and projecting a source;

a reticle stage having a reticle table, ~~the~~ said reticle table positioned between components of ~~the~~ said optical system and housed with ~~the~~ said reticle stage within ~~the~~ said reticle chamber,

wherein ~~the~~ said reticle chamber angled opening provides access to ~~the~~ said reticle stage.

14. (Currently amended) The lithography system of claim 13, wherein ~~the~~ said reticle chamber angled opening provides access to ~~the~~ said reticle stage at substantially a center of gravity.

15. (Currently amended) The lithography system of claim 14, wherein ~~the~~ said reticle stage is removable from ~~the~~ said reticle chamber via ~~the~~ said reticle chamber angled opening.

16. (Currently amended) The lithography system of claim 14, wherein ~~the~~ said reticle stage is removable from ~~the~~ said reticle chamber via ~~the~~ said reticle chamber angled opening in a first direction which is in a plane substantially ~~horizontal~~ parallel to the reticle table.

17. (Currently amended) The lithography system of claim ~~13~~ 18, wherein ~~the~~ said reticle chamber

maintenance panel is pivotably mounted to the reticle chamber.

18. (Currently amended) The lithography system of claim ~~13~~ 16, wherein ~~the~~ said reticle ~~angled~~ chamber angled opening is at an angle of approximately 45° with relation to ~~the~~ said reticle chamber such that ~~the~~ said reticle chamber maintenance panel is removed, ~~the~~ said reticle stage partially extends from ~~the~~ said reticle chamber.

19. (Currently amended) The lithography system of claim ~~13~~ 16, further comprising a body structure which is mounted to a lower portion of ~~the~~ said reticle chamber, ~~the~~ said projection optic and ~~the~~ said illuminator optic being mounted to ~~the~~ said body structure during the removal of ~~the~~ said reticle table and ~~the~~ said reticle stage.

20. (Currently amended) The lithography system of claim ~~13~~ 18, wherein ~~the~~ said reticle chamber maintenance panel is semi-cylindrically shaped.

21. (New) The lithography system of claim 1, further comprising a reticle chamber maintenance panel,

wherein said reticle chamber maintenance panel is removably mounted to said reticle chamber over said reticle chamber angled opening.